

L Number	Hits	Search Text	DB	Time stamp
4	2983	(438/127,612,760,778).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:08
5	250	((438/127,612,760,778).CCLS.) and (epoxy adj4 resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:08
6	18	((438/127,612,760,778).CCLS.) and (epoxy adj4 resin)) and "silicon oxide"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:08
7	1513	(525/109,523).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:22
8	896	((525/109,523).CCLS.) and (epoxy adj4 resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:23
9	11	((525/109,523).CCLS.) and (epoxy adj4 resin)) and "silicon oxide"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:23
10	1		USPAT	2002/06/18 09:16
11	2260	(528/10,93,94,106,395).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:25
12	598	((528/10,93,94,106,395).CCLS.) and (epoxy adj4 resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:26
13	8	((528/10,93,94,106,395).CCLS.) and (epoxy adj4 resin)) and "silicon oxide"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:26
14	44	(523/425).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:26
15	31	((523/425).CCLS.) and (epoxy adj4 resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:26
16	0	((523/425).CCLS.) and (epoxy adj4 resin)) and "silicon oxide"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/18 09:26

06/18/2002

Serial No.:09/844,855

FILE 'REGISTRY' ENTERED AT 08:55:12 ON 18 JUN 2002
E SILOXIRANE/CN
L1 1 S E2

FILE 'HCAPLUS' ENTERED AT 08:56:15 ON 18 JUN 2002
L2 10 S SILOXIRANE
L3 1 S SILOXIRAN
L4 0 S L1

FILE 'REGISTRY' ENTERED AT 09:01:29 ON 18 JUN 2002
STRUCTURE UPLOADED
L5 2 S L5 SSS SAM
L6 3 S L5 SSS FULL
L7

FILE 'HCAPLUS' ENTERED AT 09:05:13 ON 18 JUN 2002
L8 3 S L7

FILE 'REGISTRY, MARPAT, MARPATPREV, CAPLUS' ENTERED AT 09:06:15 ON 18 JUN
2002
L9 2 S L7 SSS SAM FILE=REGISTRY
L10 0 S L9 SSS SAM FILE=MARPAT

FILE 'MARPAT' ENTERED AT 09:07:03 ON 18 JUN 2002
L11 0 S L7

FILE 'USPATFULL, IFIPAT, IFIUDB' ENTERED AT 09:07:47 ON 18 JUN 2002
L12 3 S L7
L13 0 S L12 NOT L8

FILE 'BEILSTEIN' ENTERED AT 09:09:12 ON 18 JUN 2002
=> S L7
L14 0 L7

L2 ANSWER 1 OF 10 HCAPLUS COPYRIGHT 2002 ACS

AN 2001:398133 HCAPLUS

DN 135:227032

TI The gas-phase reaction of silylene with acetaldehyde. Part 1. Direct rate studies, isotope effects, RRKM modeling and ab initio studies of the potential energy surface

AU Becerra, R.; Cannady, J. P.; Walsh, R.

CS Instituto de Quimica Fisica "Rocasolano," CSIC, Madrid, 28006, Spain

SO Physical Chemistry Chemical Physics (2001), 3(12), 2343-2351

CODEN: PPCPFQ; ISSN: 1463-9076

PB Royal Society of Chemistry

DT Journal

LA English

AB Time-resolved studies of the title reaction, employing both SiH₂ and SiD₂, have been carried out over the pressure range 1-100 Torr (with SF₆ as bath gas) at five temps. in the range 297-599 K, using laser flash photolysis to generate and monitor both silylene species. The second order rate consts. obtained were pressure dependent indicating that the reaction is a third-body assisted assocn. process. The high pressure rate consts., obtained by extrapolation, gave the following Arrhenius parameters: $\log(A/\text{cm}^3 \text{ mol}^{-1} \text{ s}^{-1}) = -10.10 \pm 0.06$, $E_a = -3.91 \pm 0.47 \text{ kJ mol}^{-1}$, where the uncertainties are single std. deviations. The parameters are consistent with a fast assocn. process occurring at close to the collision rate. RRKM modeling, based on a transition state appropriate to formation of a three-membered ring product, 3-methylsiloxirane, and employing a weak collisional deactivation model gives reasonable fits to the pressure dependent curves for $\Delta H^\ddagger/\text{kJ mol}^{-1}$ in the range -215 to -245. Ab initio calcns. at the G2 level indicate the initial formation of a silacarbonyl ylid which can then either form the siloxirane by ring closure, rearrange to form siloxyethene or give ethoxysilylene. Fuller details of the potential surface are given. The energetics are reasonably consistent with siloxirane formation representing the main pathway. The isotope effects are small and close to unity, indicating that secondary isotopic label scrambling, by the reversible ring opening of the siloxirane to ethoxysilylene is not occurring. Differences with the silirane system can be explained by the stabilization of a silylene by an alkoxy substituent.

RE.CNT 42 THERE ARE 42 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

=> D BIB AB HITSTR 2-10

L2 ANSWER 2 OF 10 HCAPLUS COPYRIGHT 2002 ACS

AN 2000:612930 HCAPLUS

DN 133:181214

TI Pump housing coated with polymer and method therefor

IN Choe, Sung-Soo

PA Daewoo Electronics Co., S. Korea

SO Repub. Korea, No pp. given

CODEN: KRXXFC

DT Patent

LA Korean

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	KR 131532	B1	19980417	KR 1994-30018	19941116

AB The inner rough surface(2) of the hot water circulating pump housing (1) made of cast iron is defatted by washing, dried, coated primarily with tar epoxy at room temp. for 7-8 h, and coated secondarily with a **siloxirane** compd. to form double-layered anticorrosive polymer wherein tar epoxy layer and **siloxirane** compd. layer are 100 .mu.m thick and 80-120 .mu.m thick, resp.

L2 ANSWER 3 OF 10 HCAPLUS COPYRIGHT 2002 ACS

AN 1999:322771 HCAPLUS

DN 131:73278

TI Gas-Phase Reaction of Silylene with Acetone: Direct Rate Studies, RRKM Modeling, and ab Initio Studies of the Potential Energy Surface

AU Becerra, R.; Cannady, J. P.; Walsh, R.

CS Instituto de Quimica Fisica Rocasolano, CSIC, Madrid, 28006, Spain

SO Journal of Physical Chemistry A (1999), 103(23), 4457-4464

CODEN: JPCAFH; ISSN: 1089-5639

PB American Chemical Society

DT Journal

LA English

AB Time-resolved studies of the title reaction were carried out over the pressure range 3-100 torr (with SF6 as bath gas) at 5 temps. in the range 295-602 K, using laser flash photolysis to generate and monitor silylene, SiH2. The 2nd-order rate consts. obtained were pressure-dependent, indicating that the reaction is a 3rd-body-assisted assocn. process. The high-pressure rate consts., obtained by extrapolation, gave the following Arrhenius parameters: $\log(A/\text{cm}^3 \text{ mol}^{-1} \text{ s}^{-1}) = -10.17 \pm 0.04$ and $E_a = -4.54 \pm 0.32 \text{ kJ mol}^{-1}$, where the uncertainties are single std. deviations. The parameters are consistent with a fast assocn. process occurring at close to the collision rate. RRKM modeling, based on a transition state appropriate to formation of a 3-membered ring product, 3,3-dimethylsiloxirane, and employing a weak collisional deactivation model, gives reasonable fits to the pressure-dependent curves for .DELTA.H.degree./kJ mol⁻¹ in the range -205 to -225. Ab initio calcns. at the G2 level indicate the initial formation of a silacarbonyl ylide, which can then either form the **siloxirane** by ring closure or rearrange to form 2-siloxypopene. Fuller details of the potential surface are given. The energetics are consistent with **siloxirane** formation representing the main pathway.

theoretical
✓

RE.CNT 49 THERE ARE 49 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L2 ANSWER 4 OF 10 HCAPLUS COPYRIGHT 2002 ACS

AN 1998:777071 HCAPLUS

DN 130:84306

TI Interpretation of temporary impedance increases of steel/polymer coating systems in electrolytes

AU Klenowicz, Zbigniew; Miszczuk, Andrzej; Darowicki, Kazimierz

CS Politech. Gdanska, Gdansk, 80-952, Pol.

SO Prace Naukowe Instytutu Technologii Nieorganicznej i Nawozow Mineralnych Politechniki Wroclawskiej (1998), 46, 143-148

CODEN: PNPWAP; ISSN: 0084-2893

PB Oficyna Wydawnicza Politechniki Wroclawskiej

DT Journal

LA Polish

AB Examples of temporary impedance heightening of coating systems having 60-1800 gm in thickness during exposure to 3% NaCl, 36% HCl and 40% NaOH at room temp. and to 70% H2SO4 at 353K are presented. Three types of coatings were tested, namely vinyl, epoxy and **siloxirane**. The possible reasons of such spontaneous impedance increases were analyzed.

Possibilities of coating tightness improvements due to polymn., swelling, filling of pores with hydrogen evolved or self healing with corrosion products were taken into account. Filling the pores with rust formed as a result of corrosion reaction performed at the pore bottoms is with the highest probability the reason of spontaneous impedance growth during exposure.

L2 ANSWER 5 OF 10 HCAPLUS COPYRIGHT 2002 ACS
AN 1998:387441 HCAPLUS
DN 129:69204

TI New generation of polymer lining systems for cargo tanks

AU Keehan, D. J.

CS Advanced Polymer Sciences Inc., Avon, OH, USA

SO British Corrosion Journal (1997) 32(3), 174-178

CODEN: BCRJA3; ISSN: 0007-0599

PB Institute of Materials

DT Journal

LA English

AB Advanced Polymer Sciences (APS) originally developed **Siloxirane**, a patented multifunctional polymer with a high d. crosslinked structure, to meet the extremely demanding anticorrosion and surface protection requirements of the military and aerospace industries. The superior performance of the material has also made it attractive as a coating in a wide range of marine and industrial applications. Not the least of these is its use as the lining material for the cargo tanks of seagoing chem. tankers, an area in which there were no real technol. advances for .gtoreq.20 yr. Researchers at APS have conducted .gtoreq.5000 tests on **Siloxirane** - as well as conventional coating systems such as epoxies, zinc silicates, vinyl esters, rubbers, and phenolics - to test phys. properties and chem. resistance for an extensive range of products, including those commonly carried by sea.

L2 ANSWER 6 OF 10 HCAPLUS COPYRIGHT 2002 ACS

AN 1997:145190 HCAPLUS

DN 126:157542

TI Experimental and Theoretical Characterization of $\text{FSi}(\text{OCH}_3)_2(\text{OCH}_2)^-:$ A Gas Phase Fluoride-**Siloxirane** Adduct

AU Morgon, Nelson H.; Argenton, Andre B.; da Silva, Maria L. P.; Riveros, Jose M.

CS Institute of Chemistry, University of Sao Paulo, Sao Paulo, 05599-970, Brazil

SO J. Am. Chem. Soc. (1997), 119(7), 1708-1716

CODEN: JACSAT; ISSN: 0002-7863

PB American Chemical Society

DT Journal

LA English

AB The structural characteristics and reactivity of the gas-phase $\text{FSi}(\text{OCH}_3)_2(\text{OCH}_2)^-$ ion were studied by a combination of ab initio calcns. and FT-ICR techniques. The theor. calcns. for different possible structures reveal that carbanion and alkoxide ion type structures lead to ring closure upon geometry optimization to yield two different cyclic fluoride-**siloxirane** structures. The $\text{FSi}(\text{OCH}_3)_2(\text{cyc-OCH}_2)^-$ ions contg. the elusive **siloxirane** ring are extremely stable with respect to F- (69 kcal mol⁻¹) dissocn. in agreement with earlier calcns. on simpler systems. Exptl., this ion is formed as a minor product (7%) in the gas-phase ion/mol. reaction of F- with $\text{Si}(\text{OMe})_4$ and undergoes readily fluoride transfer to the parent neutral. This strongly suggests an ion with a structure corresponding to a fluoride adduct of a **siloxirane** species. Reaction of $\text{FSi}(\text{OCH}_3)_2(\text{OCH}_2)^-$ with BF_3 ,

hexafluorobenzene, and gas-phase acids more acidic than EtOH further suggests that this ion is capable of reacting as an alkoxide type nucleophile or base. This latter behavior was assocd. with the possibility of ring opening of the **siloxirane** in the collision complex that mediates this ion/mol. reaction.

L2 ANSWER 7 OF 10 HCAPLUS COPYRIGHT 2002 ACS
AN 1996:716883 HCAPLUS
TI **Siloxirane** based polymer coating for slop tanks
AU Anon.
SO Br. Corros. J. (1996), 31(3), 168
CODEN: BCRJA3; ISSN: 0007-0599
DT Journal; Miscellaneous
LA English
AB Unavailable

L2 ANSWER 8 OF 10 HCAPLUS COPYRIGHT 2002 ACS
AN 1996:259696 HCAPLUS
DN 125:10921
TI Reactions of a Silanediyl with Carbon-Oxygen and Carbon-Nitrogen Double Bonds
AU Belzner, Johannes; Ihmels, Heiko; Pauletto, Lara; Noltemeyer, Matthias
CS Institut fuer Organische Chemie, Georg-August-Universitaet, Goettingen, D-37077, Germany
SO J. Org. Chem. (1996), 61(10), 3315-19
CODEN: JOCEAH; ISSN: 0022-3263
DT Journal
LA English
OS CASREACT 125:10921
AB Silanediyl ((2-(Me2NCH2)C6H4)2Si: or Ar2Si:, 2) (generated by thermolysis of the corresponding cyclotrisilane) reacts with benzophenone, tetracyclone, and fluorenone to yield products I (X = O), II and III, resp., which may originate from highly reactive **siloxiranes** as intermediates. However, using adamantanone as ketone, stable **siloxirane** IV was obtained. The interaction of 2 with benzophenone anil or fluorenone 2,6-dimethylanil gives heterocyclic compds. I (X = NH) and V, resp. The involvement of silaziridines in these reactions, as well as in the reactions of 1 with 1,4-diaza-1,3-butadienes, which yield the expected formal [4 + 1] cycloaddn. products VI (R = tBu, cyclohexyl), remains questionable. Results of x-ray crystallog. structure detns. of II and VI (R = tBu) are available form the Cambridge Crystallog. Data Center.

L2 ANSWER 9 OF 10 HCAPLUS COPYRIGHT 2002 ACS
AN 1994:220444 HCAPLUS
DN 120:220444
TI New generation polymers to replace epoxies, vinyl esters, and phenolics
AU Keehan, Donald J.
CS Adv. Polym. Sci., Inc., Australia
SO Conf. - Australas. Corros. Assoc. (1991), 31st(Corrosion 91), Paper C5, 14 pp.
CODEN: CEANDQ; ISSN: 0729-2341
DT Journal
LA English
AB The advantages of chem. resistant polymers based on pentafunctional (arom. oxirane) end-capped cyclic Si oxide (**Siloxirane**), as coatings, over epoxy, epoxy acrylate, and bismaleimide resins were discussed.

L2 ANSWER 10 OF 10 HCAPLUS COPYRIGHT 2002 ACS

06/18/2002

Serial No.:09/844,855

AN 1993:451370 HCAPLUS
DN 119:51370
TI AC-impedance measurements on coatings for desulfurization plants
AU Oestergaard, M. J. L.; Visgaard, A.; Maahn, E.
CS Mater. Dep., Risoe Natl. Lab., Roskilde, 4000, Den.
SO Surf. Coat. Int. (1993), 76(1), 29-30, 32-4, 36-9
CODEN: SCOIE6
DT Journal
LA English
AB Degradn. of coatings (glass flake-filled vinyl ester resins, chlorinated butyl rubber, epoxy, siloxane, fluoropolymer, fluoro-contg. rubber) for FGD plants was investigated by impedance measurements. The resistance of coatings is high and the capacitance low as long as the coating does not show any degradn. When degradn. begins, impedance measurements quickly indicate changes in resistance and capacitance even if the damage zones are small. The impedance measurements indicate also degradn. trends in coatings; in some cases, degradn. starts with formation of pores with further diffusion-controlled electrochem. processes. These processes manifest as a drastic decrease in the resistance and increase in total impedance and phase angle at low frequencies when the process is controlled by diffusion. In other cases, the impedance decreased at low frequencies, which was attributed to formation of active sites in the form of blisters or cracks. Control of use of rubber coatings in 3% Cl solns. is recommended since degradn. can begin after short exposure time (about 80 days). Glass filled-vinyl esters withstand this media in the studied temp. range. Degradn. of coatings in 70% H2SO4 at 100.degree. starts immediately and ends by complete disappearance of coatings in 4-7 days. Glass-filled vinyl ester coatings withstand H2SO4 media during 50 days. It was impossible to perform electrochem. measurements of **siloxirane** coating due to the absence of the electrolytic contact through the coating under the studied conditions.

06/18/2002

Serial No.:09/844,855

L3 ANSWER 1 OF 1 HCAPLUS COPYRIGHT 2002 ACS
AN 1996:73220 HCAPLUS
DN 124:120289
TI Hybrid prepolymer-based coatings and their manufacture
IN Sakurai, Kazuhisa; Oana, Tomoharu; Aihara, Tetsuo
PA Abc Trading Co, Japan
SO Jpn. Kokai Tokkyo Koho, 7 pp.
CODEN: JKXXAF

DT Patent
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
	-----	----	-----	-----	-----
PI	JP 07292315	A2	19951107	JP 1994-83425	19940421
AB	In order to adjust the viscosity without impairing the prepolymer properties, title coatings contain polyepoxy diluents and amine hardeners. A mixt. of <u>Siloxiran (cyclic silicone/epoxy resin hybrid prepolymer)</u> 100, neopentyl glycol diglycidyl ether 20, and a modified aliph. polyamine 25 showed 20.degree. viscosity 2500 cP, pencil hardness 4, and good chem. (concd. H2SO4, Me2CO, and MEK) resistance.				

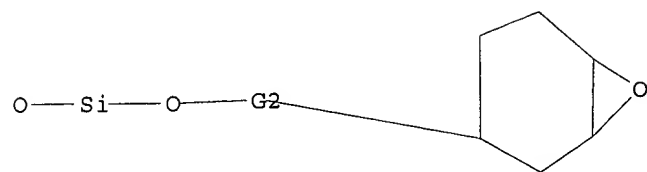
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Serial No.:09/844,855

=> D L5

L5 HAS NO ANSWERS

L5 STR



G1 Ak,H

G2 Cy,Ak

06/18/2002

Serial No.:09/844,855

L8 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2002 ACS

AN 1996:106720 HCAPLUS

DN 124:261966

TI Selective monoaddition to siloxanes and poly(dihydrosiloxanes) as intermediates or coating precursors

IN Crivello, James V.

PA Polyset Company, Inc., USA

SO U.S., 9 pp.

CODEN: USXXAM

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 5484950	A	19960116	US 1992-993689	19921221
OS	MARPAT 124:261966				

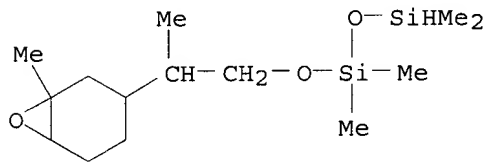
AB An olefin, e.g. 3-vinyl-7-oxabicyclo[4.1.0]heptane (I) or acetylene is added to a siloxane which contains 2 reactive Si-H bonds to produce unsym. siloxanes (monoaddn. product) from sym. dihydrosiloxanes. A second olefin or acetylene may be added to the remaining H terminal group to produce a product with two functional groups, e.g. diepoxide compd. Thus, 1,1,3,3-tetramethyldisiloxane (0.1 mol) and I (0.05 mol) were heated at 50-55.degree. for 3 h in the presence of Pt hydrosilation catalyst to give a product b. 65.degree. (0.03 mm Hg).

IT 175647-04-8P

RL: IMF (Industrial manufacture); PREP (Preparation)
(selective monoaddn. to siloxanes for functional intermediates or coating precursors)

RN 175647-04-8 HCAPLUS

CN Disiloxane, 1,1,3,3-tetramethyl-1-[2-(1-methyl-7-oxabicyclo[4.1.0]hept-3-yl)propoxy]- (9CI) (CA INDEX NAME)



=> D BIB AB HITSTR 2-3

L8 ANSWER 2 OF 3 HCAPLUS COPYRIGHT 2002 ACS

AN 1987:18807 HCAPLUS

DN 106:18807

TI Aminosilane coupling agents

IN Inokuchi, Hiroichi; Watanabe, Akihiko; Yoshida, Shinjiro; Yoshii, Tadashi; Yonaiyama, Hiroshi

PA Nitto Boseki Co., Ltd., Japan; Nippon Unicar Co., Ltd.

SO Jpn. Kokai Tokkyo Koho, 7 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

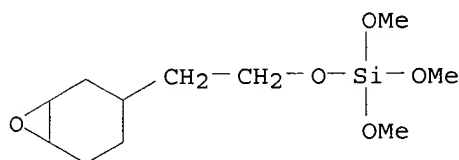
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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06/18/2002

Claim 2

Serial No.: 09/844,855

PI JP 61112086 A2 19860530 JP 1984-233677 19841106
 JP 01013714 B4 19890307
 OS CASREACT 106:18807
 AB The title coupling agents comprise aminosilanes (RNHZNR1Z1Z2)mSi(OR2)4-m
 (I; Z = arom. hydrocarbon group; Z1 = hydrocarbon group; Z2 = C1-6 aliph.
 hydrocarbon group; R = H, C1-4 hydrocarbon group; R1 = H, C1-4 hydrocarbon
 group, arom. hydrocarbon group; R2 = H, C1-4 hydrocarbon group; m = 1-3)
 and/or I hydrohalides. I are heat-resistant and are suitable for treating
 glass fibers in the manuf. of laminates for electronic parts. Thus, 297.5
 parts 4,4'-diaminodiphenylmethane and 832.9 parts Me2SO were heated to
 130.degree. under N, 369.6 g .beta.-(3,4-epoxycyclohexyl)ethyltrimethoxysi
 lane was added dropwise over 1 h, and the mixt. was refluxed at
 130.degree. for .gtoreq.10 h to give I (R, R1 = H, R2 = Me, Z =
 4,4'-C6H4CH2C6H4, Z1 = 6-hydroxy-1,3-cyclohexylidene, Z2 = CH2CH2, m = 1).
 Laminate prepd. from Epikote 1045-A-70 and glass cloth impregnated with I
 showed no change in a pressure cooker test at 133.degree. after 180 min,
 and water absorption of 0.81% after 24-h immersion in H2O following the
 test.
 IT 105822-30-8
 RL: RCT (Reactant)
 (reaction of, with diamines)
 RN 105822-30-8 HCAPLUS
 CN Silicic acid (H4SiO4), trimethyl 2-(7-oxabicyclo[4.1.0]hept-3-yl)ethyl
 ester (9CI) (CA INDEX NAME)



L8 ANSWER 3 OF 3 HCAPLUS COPYRIGHT 2002 ACS
 AN 1975:124742 HCAPLUS
 DN 82:124742
 TI Organosilicon compounds
 IN Foley, Kevin M.; Vigo, Francesco M.
 PA Owens-Corning Fiberglas Corp.
 SO Ger. Offen., 69 pp.
 CODEN: GWXXBX
 DT Patent
 LA German
 FAN.CNT 4

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 2415395	A1	19741017	DE 1974-2415395	19740329
	US 3931266	A	19760106	US 1973-347241	19730402
	BE 813082	A1	19740715	BE 1974-142669	19740329
	FR 2223376	A1	19741025	FR 1974-11025	19740329
	JP 49127928	A2	19741207	JP 1974-37313	19740402
	GB 1419912	A	19751231	GB 1974-14594	19740402
PRAI	US 1973-347241		19730402		
AB	Complex siloxanes (26) were prepd. by treating a Si halide with a monoepoxide and a polyepoxide. Thus, SiCl4 was treated with 3 epoxide equivs. PhOZ (Z = glycidyl), then with 2 epoxide equivs. ZO(CH2)4OZ, and				

06/18/2002

Serial NO.:09/844,855

the whole kept 1 hr to give a mixt. from which
(PhOCH₂CHClCH₂O)₃SiOCH₂CHClCH₂O(CH₂)₄OZ could be isolated.

IT 54898-93-0P

RL: SPN (Synthetic preparation); PREP (Preparation)
(prepn. of)

RN 54898-93-0 HCAPLUS

CN Silicic acid (H₄SiO₄), 2-chloro-2-(7-oxabicyclo[4.1.0]hept-3-yl)ethyl
tris[2-chloro-3-(2-propenyloxy)propyl] ester (9CI) (CA INDEX NAME)

